UNITED STATES PATENT AND TRADEMARK OFFICE **CERTIFICATE OF CORRECTION**

PATENT NO. : 6,936,484 B2

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INVENTOR(S) : Masakazu Kanechika et al.

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

Column 46,

Line 20, Claim 16 should read:

-- A method as defined in claim 15, wherein the semiconductor material substrate or layer comprises silicon; the first impurity is oxygen; and the second impurity is boron. --.

Signed and Sealed this

Third Day of January, 2006

JON W. DUDAS Director of the United States Patent and Trademark Office